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	Application No.	Applicant(s)	
Notice of Allowability	10/708,936	CHASE ET AL.	
	Examiner	Art Unit	
	Heather A. Doty	2813	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT IN of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in is) or other appropriate comm RIGHTS. This application is:	n this application. If not included unication will be mailed in due course. THIS	
1. \boxtimes This communication is responsive to <u>the amendment date</u>	ed 3/13/2006.		
2. X The allowed claim(s) is/are <u>8-12</u> .			
 Acknowledgment is made of a claim for foreign priority of a) All b) Some* c) None of the: Certified copies of the priority documents have Certified copies of the priority documents have Copies of the certified copies of the priority documents have Copies of the certified copies of the priority documents have Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE 	re been received. re been received in Application ocuments have been received of this communication to file	on No d in this national stage application from the	:
noted below. Failure to timely comply will result in ABANDON THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 4. A SUBSTITUTE OATH OR DECLARATION must be subj	nitted. Note the attached EX		
INFORMAL PATENT APPLICATION (PTO-152) which gives 5. CORRECTED DRAWINGS (as "replacement sheets") muse (a) including changes required by the Notice of Draftspeent (b) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examine Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in 6. DEPOSIT OF and/or INFORMATION about the depattached Examiner's comment regarding REQUIREMENT	ust be submitted. rson's Patent Drawing Revie r's Amendment / Comment o 1.84(c)) should be written on t the header according to 37 Cl osit of BIOLOGICAL MAT	w (PTO-948) attached r in the Office action of the drawings in the front (not the back) of FR 1.121(d). ERIAL must be submitted. Note the	
 Attachment(s) 1. ☐ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB Paper No./Mail Date 3/30/2006 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material 	6. ☐ Interview S Paper No. /08), 7. ☐ Examiner's	oformal Patent Application (PTO-152) ummary (PTO-413), /Mail Date Amendment/Comment Statement of Reasons for Allowance CAL UNITEHEA, JR. SUPERMSDRY PATENT DAMMER.	`

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DETAILED ACTION

Allowable Subject Matter

Claims 8-12 are allowed.

The following is an examiner's statement of reasons for allowance:

Prior art does not teach or suggest, in combination with the other claimed limitations, removing the first and second exposed regions of the first and second oxide layers under the oxide mask. As detailed in the previous Office action, Schaefer et al., the closest prior art of record, teaches removing a LOCOS oxide mask, but does not teach the presence of an underlying oxide layer. Moon et al. teaches that it is standard in LOCOS to form a pad oxide layer beneath the LOCOS oxide. However, Moon et al. does not teach removing either the LOCOS layer or the underlying pad oxide layer, so it would not be reasonable to combine Moon et al. with Schaefer et al. to teach the removal of the oxide layer underlying the oxide mask (Schaefer et al. does not teach the presence of the underlying oxide, and Moon et al. does not teach its removal).

Furthermore, Schaefer et al. does not teach that some of the processing steps are performed on single wafers while others are performed in batch, although Schaefer et al. does teach most of the claimed process steps, and teaches them in the order in which they are recited in claim 8. Although it is known in the art of semiconductor processing to perform some processing steps on single wafers and others in batch, there would be no motivation to combine other relevant prior art with Schaefer et al. to arrive at the invention as claimed such that the batch processing steps specifically begin with removing the first and second mask patterns.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Heather A. Doty, whose telephone number is 571-272-8429. The examiner can normally be reached on M-F, 8:30 - 5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead, Jr., can be reached at 571-272-1702. The fax number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.